

CORRECTED VERSION

(19) World Intellectual Property Organization
International Bureau



(43) International Publication Date
17 January 2008 (17.01.2008)

PCT

(10) International Publication Number
WO 2008/008497 A1

(51) International Patent Classification:

B01D 53/04 (2006.01) **B01D 46/00** (2006.01)

(21) International Application Number:

PCT/US2007/016011

(22) International Filing Date: 13 July 2007 (13.07.2007)

(25) Filing Language: English

(26) Publication Language: English

(30) Priority Data:

60/830,737 13 July 2006 (13.07.2006) US

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(81) Designated States (unless otherwise indicated, for every kind of national protection available): AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BH, BR, BW, BY, BZ, CA, CH,

CN, CO, CR, CU, CZ, DE, DK, DM, DO, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT, HN, HR, HU, ID, IL, IN, IS, JP, KE, KG, KM, KN, KP, KR, KZ, LA, LC, LK, LR, LS, LT, LU, LY, MA, MD, ME, MG, MK, MN, MW, MX, MY, MZ, NA, NG, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RS, RU, SC, SD, SE, SG, SK, SL, SM, SV, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, ZA, ZM, ZW.

(84) Designated States (unless otherwise indicated, for every kind of regional protection available): ARIPO (BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW), Eurasian (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European (AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LT, LU, LV, MC, MT, NL, PL, PT, RO, SE, SI, SK, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).

Declarations under Rule 4.17:

- as to applicant's entitlement to apply for and be granted a patent (Rule 4.17(ii))
- as to the applicant's entitlement to claim the priority of the earlier application (Rule 4.17(iii))
- of inventorship (Rule 4.17(iv))

Published:

- with international search report

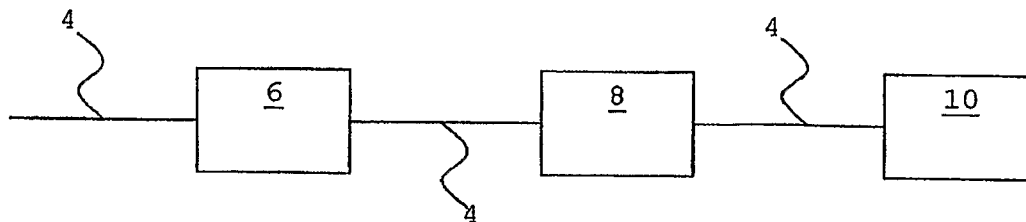
(48) Date of publication of this corrected version:

2 May 2008

(15) Information about Correction:

see Notice of 2 May 2008

(54) Title: FILTERING SYSTEM FOR A SEMICONDUCTOR PROCESSING TOOL



(57) Abstract: The present invention provides a filtering system for a semiconductor processing tool. In one embodiment, the filtering system is associated with the semiconductor processing tool. A system of the invention comprises a first and second filter layer in fluid communication with a gas flow path. The flow path is a gas stream comprising volatile silica containing compounds such as hexamethyldisiloxane and trimethylsilanol. The gas flow path passes through the first and second filter layer to fluidly communicate with the semiconductor processing tool. Preferably, the first filter layer of the filtering system is upstream along the gas flow path from the second filter layer. The medias of the first and second filter layers are selected and arranged based on given contaminant concentrations. The invention also provides a method for filtering gas containing hexamethyldisiloxane and trimethylsilanol in communication with a semiconductor processing tool, which employs a system comprising a first and second filter layer.

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